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Applicant(s): Yasushi AKIYAMA et al.

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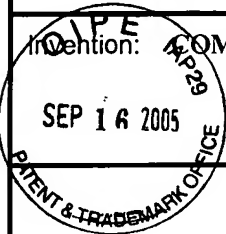
WU, Ives J.

Group Art Unit

1713

Invention: **COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME**

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PATENT ABSTRACTS OF JAPAN

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(21)Application number : 60-201524 (71)Applicant : HITACHI LTD

(22)Date of filing : 13.09.1985 (72)Inventor : TANAKA TOSHIHIKO

SHIRAIISHI HIROSHI

HASEGAWA NOBUO

HAYASHIDA TETSUYA

(54) PATTERN FORMING METHOD

(57)Abstract:

PURPOSE: To form an ultrafine and accurate pattern and a pattern having high alignment accuracy by forming a perfluoroalkyl polyester film or perfluoroalkylamine film or their mixture film on a resist.

CONSTITUTION: A perfluoroalkyl polyether film, a perfluoroalkylamine film or their mixture film (perfluoroalkyl compound) is formed on a resist before exposing, and the perfluoroalkyl compound film is removed after exposing. The perfluoroalkyl compound film is transparent and its refractive index is approx. 1.3. Therefore, it serves as a resist reflection preventive film. Reflected light on the resist surface is reduced without loss of the incident light amount by the transparent reflection preventive film to prevent the pattern dimension accuracy from decreasing owing to the multiple interference of light in the resist film. It also reduces the deterioration of a pattern detection signal.

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